Technical Bulletin

SurfTechs 4583 AFS

DESCRIPTION

SurfTechs 4583 AFS is a unique hydrophilic silicone based polymer formulated to lend excellent durable water absorbency on cellulosic and synthetic fabrics, especially polyester. The product may be used on fabrics and garments to lend moisture management characteristics.

BENEFITS

SurfTechs 4583 AFS has the following beneficial characteristics.

- Provides High Level of Absorbency
- Effective at Low Add-On Level
- Launder and Dry Clean Durable
- Resin and Extender Compatible

TYPICAL PROPERTIES

Color White
Texture Liquid
PH About 6
Specific Gravity About 1.02
Solubility Soluble

PREPARATION

SurfTechs 4583 AFS is ready to use. The product can be combined with **SurfTechs 4142** for increased durability.

APPLICATION

SurfTechs 4583 AFS should be applied by pad application as follows:

SurfTechs 4583 AFS 5 – 10% OWB

or

 SurfTechs 4583 AFS
 3 – 5% OWB

 SurfTechs 4142
 3 – 5% OWB

Note: Fabrics or garments must be very well prepared. Residual size, alkali or other chemicals will interfere with performance. Fabrics or garments should be slightly acidic for best results.

STORAGE

SurfTechs 4583 AFS should be stored in a cool, dry and well-ventilated area.

HANDLING

Follow good industrial hygiene when handling **SurfTechs 4583 AFS**. Please refer to the Material Safety Data Sheet for details.

PACKAGING

SurfTechs 4583 AFS is available in drums and totes.

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